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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

CHEVALIER et al

Atty. Ref.: **2590-144**

Serial No. **Unknown**

Group:

National Phase of: **PCT/CH2004/000300**

International Filing Date: **18 May 2004**

Filed: **Herewith**

Examiner:

For: **A HIGH DENSITY PLASMA REACTOR**

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November 22, 2005

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

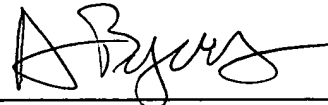
As suggested by 37 C.F.R. 1.97, the undersigned attorney brings to the attention of the Patent and Trademark Office the references listed on the attached form PTO/SB/08a. Copies of the non-U.S. references are enclosed. This is not to be construed as a representation that a search has been made or that no better prior art exists, or that a reference is relevant merely because cited. A copy of the International Search Report is also enclosed.

The Examiner is requested to initial the attached form PTO/SB/08a and to return a copy of the initialed document to the undersigned as an indication that the attached references have been considered and made of record.

Respectfully submitted,

NIXON & VANDERHYE P.C.

By: _____



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APPLICANT

CHEVALIER et al

(Use several sheets if necessary)

FILING DATE

GROUP

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U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (including Author, Title, Date, Pertinent pages, etc.)

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| | | PATENT ABSTRACTS OF JAPAN, vol. 2000, no. 08 6 October 2000 & JP 2000 150483, 30 May 2000 |
| | | International Search Report |
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*Examiner

Date Considered

Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.